L Number	Hits	Search Text	DB	Time stamp
- Manber	67	datum near platen	USPAT	2003/08/08
-	1	(datum near platen) and wafer	USPAT	2002/11/05
-	1873	(standard reference calibrat\$3) near wafer	USPAT	13:49 2002/11/05 13:49
-	0	((standard reference calibrat\$3) near wafer) near slice	USPAT	2002/11/05
-	0	((standard reference calibrat\$3) near wafer) near strip	USPAT	2002/11/05
-	4		USPAT	2002/11/05 13:50
-	201	(359/509).CCLS.	USPAT	2002/11/05 14:06
-	4	((359/509).CCLS.) and venturi	USPAT	2002/11/05
-	320	venturi and wafer	USPAT	14:07 2002/11/05
-	1	("6218320").PN.	USPAT	14:08 2003/03/07
-	1	("5503875").PN.	USPAT	15:44 2003/03/07
_	1	("5679165").PN.	USPAT	15:44 2003/03/07
-	1	("6495805").PN.	USPAT	15:45 2003/03/07
_	4		USPAT	15:47 2003/03/07
_	0	, , , , , , , , , , , , , , , , , , , ,	USPAT	15:45 2003/03/07
		(("5679165").PN.) (("6495805").PN.)) and (lens window)		15:45
	32	("4602981") or ("5254367") or ("5336356") or ("5478455") or ("5534359") or ("5578504") or ("5578505") or ("5665214") or ("5665905") or ("5693178") or ("5755877") or ("5789734") or ("5818596") or ("5841110") or ("5899702") or ("5953578") or ("5955139") or ("5960255") or ("5994676") or ("6030887") or ("6083833") or ("6086734") or ("6121622") or ("6136712") or ("6131052") or ("6136712") or ("6147020") or ("6159388") or ("6211094") or ("6218264") or ("6211094")).PN.	USPAT	2003/03/07
-	12	(("6250914") or ("6267158") or ("6331890") or ("6414280") or ("6435869") or ("6451674") or ("6472639") or ("6495805") or ("4383907") or ("5273424") or ("5421190") or ("5552888")).PN.	USPAT	2003/03/07 15:49
	44	((("5851842") or ("6051844") or ("4602981") or ("5254367") or ("5336356") or ("5478455") or ("5534359") or ("5578504") or ("5578505") or ("5665214") or ("5665905") or ("5693178") or ("5755877") or ("5789734") or ("5818596") or ("5841110") or ("5899702") or ("5953578") or ("5955139") or ("5960255") or ("5994676") or ("6030887") or ("6088833") or ("6086734") or ("6121622") or ("6123766") or ("6131052") or ("6136712") or ("6147020") or ("6159388") or ("6211094") or ("6218264") or ("6211094")).PN.) (("6250914") or ("6472639") or ("6495805") or ("6438890") or ("6472639") or ("6495805") or ("4383907") or ("5273424") or ("5421190") or ("5552888")).PN.)	USPAT	2003/03/07

Search History 8/10/03 9:33:27 PM Page 1

	17	////// 051942!!\ 07 /!! 6051944!!\ 07	TICDAM.	2002/02/07
-	17	(((("5851842") or ("6051844") or ("4602981") or ("5254367") or ("5336356")	USPAT	2003/03/07
		or ("5478455") or ("5534359") or		13.34
		("5578504") or ("5578505") or ("5665214")		
ĺ		or ("5665905") or ("5693178") or		
		("5755877") or ("5789734") or ("5818596")		
		or ("5841110") or ("5899702") or		
		("5953578") or ("5955139") or ("5960255")		
		or ("5994676") or ("6030887") or		
		("6083833") or ("6086734") or ("6121622")		
	į	or ("6123766") or ("6131052") or		
	l	("6136712") or ("6147020") or ("6159388")		
		or ("6211094") or ("6218264") or   ("6211094")).PN.) ((("6250914") or		
		("6267158") or ("6331890") or ("6414280")		:
		or ("6435869") or ("6451674") or		
	:	("6472639") or ("6495805") or ("4383907")		
		or ("5273424") or ("5421190") or		
		("5552888")).PN.)) and (lens window)		
-	7		USPAT	2003/03/07
		("4602981") or ("5254367") or ("5336356")		15:51
		or ("5478455") or ("5534359") or		1
		("5578504") or ("5578505") or ("5665214")		
		or ("5665905") or ("5693178") or		
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}		("5953578") or ("5955139") or ("5960255") or ("5994676") or ("6030887") or	}	
		("6083833") or ("6086734") or ("6121622")		
		or ("6123766") or ("6131052") or		
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		or ("6211094") or ("6218264") or		1
		("6211094")).PN.) ((("6250914") or		
		("6267158") or ("6331890") or ("6414280")		ļ
		or ("6435869") or ("6451674") or		
		("6472639") or ("6495805") or ("4383907")		
		or ("5273424") or ("5421190") or	:	
		("5552888")).PN.)) and (lens window)) and		
		valve		
-	7		USPAT	2003/03/07
		("4602981") or ("5254367") or ("5336356")		15:51
		or ("5478455") or ("5534359") or ("5578504") or ("5578505") or ("5665214")		<u> </u>
	1	or ("5665905") or ("5693178") or		
		("5755877") or ("5789734") or ("5818596")		
	-	or ("5841110") or ("5899702") or		
ĺ		("5953578") or ("5955139") or ("5960255")		
		or ("5994676") or ("6030887") or		
1		("6083833") or ("6086734") or ("6121622")		
		or ("6123766") or ("6131052") or		
		("6136712") or ("6147020") or ("6159388")		
		or ("6211094") or ("6218264") or		
		("6211094")).PN.) ((("6250914") or		
1	1	("6267158") or ("6331890") or ("6414280")		
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	-	or ("5273424") or ("5421190") or		
	•	("5552888")).PN.)) and (lens window)) and		
		valve) and gas	1	
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-	5	(((("5851842") or ("6051844") or	USPAT	2003/03/07
	j	("4602981") or ("5254367") or ("5336356")		15:54
		or ("5478455") or ("5534359") or ("5578504") or ("5578505") or ("5665214")		.
		or ("5665905") or ("5693178") or	•	
		("5755877") or ("5789734") or ("5818596")		
		or ("5841110") or ("5899702") or		
		("5953578") or ("5955139") or ("5960255")		
		or ("5994676") or ("6030887") or		
		("6083833") or ("6086734") or ("6121622")		
		or ("6123766") or ("6131052") or		
		("6136712") or ("6147020") or ("6159388")		
		or ("6211094") or ("6218264") or ("6211094")).PN.) ((("6250914") or		
		("6211094").PN.) ((( 6230914") 61 ("6267158") or ("6331890") or ("6414280")		
		or ("6435869") or ("6451674") or		
		("6472639") or ("6495805") or ("4383907")		
		or ("5273424") or ("5421190") or		
		("5552888")).PN.)) and (lens)		
-	2	((((("5851842") or ("6051844") or	USPAT	2003/03/07
		("4602981") or ("5254367") or ("5336356")		15:54
		or ("5478455") or ("5534359") or		}
		("5578504") or ("5578505") or ("5665214")		
		or ("5665905") or ("5693178") or ("5755877") or ("5789734") or ("5818596")		
		or ("5841110") or ("5899702") or		
		("5953578") or ("5955139") or ("5960255")		
		or ("5994676") or ("6030887") or		
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		or ("6123766") or ("6131052") or		
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		or ("6211094") or ("6218264") or		
		("6211094")).PN.) ((("6250914") or ("6267158") or ("6331890") or ("6414280")		
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		or ("5273424") or ("5421190") or		
1		("5552888")).PN.)) and (lens)) and valve		
-	2	(((((("5851842") or ("6051844") or	USPAT	2003/03/07
		("4602981") or ("5254367") or ("5336356")		15:54
		or ("5478455") or ("5534359") or   ("5578504") or ("5578505") or ("5665214")		
		or ("5665905") or ("5693178") or		
		("5755877") or ("5789734") or ("5818596")		
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		("5953578") or ("5955139") or ("5960255")		
		or ("5994676") or ("6030887") or		
		("6083833") or ("6086734") or ("6121622")		
		or ("6123766") or ("6131052") or ("6136712") or ("6147020") or ("6159388")		
		or ("6211094") or ("6218264") or		
		("6211094")).PN.) ((("6250914") or		
		("6267158") or ("6331890") or ("6414280")		
		or ("6435869") or ("6451674") or		
		("6472639") or ("6495805") or ("4383907")		
		or ("5273424") or ("5421190") or		
		("5552888")).PN.)) and (lens)) and valve)		
1_	7908	and gas   deposition near chamber	USPAT;	2003/03/27
	, 500	acposition near chamber	US-PGPUB	13:00
-	64	(deposition near chamber) same lens	USPAT;	2003/03/27
1			US-PGPUB	13:05
-	0	((deposition near chamber) same lens) and	USPAT;	2003/03/27
		(datum near platen)	US-PGPUB	13:05
-	0	(datum near platen) and (deposition near	USPAT;	2003/03/27
_	79	chamber) datum near platen	US-PGPUB USPAT;	13:05   2003/03/27
	'	addan iidar praddii	US-PGPUB	13:06
-	13	(datum near platen) and (wafer	USPAT;	2003/03/27
	<u> </u>	semiconductor)	US-PGPUB	13:07

238   (deposition near chamber) and platen   USPAT;   2003/03/27   13:07   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/03/27   2003/0					
30	-	238	(deposition near chamber) and platen	USPAT;	2003/03/27
and lens  - 5 cdv and (lens same (housing chamber)) - 892 cvd and (lens same (housing chamber)) - 193 (cvd and (lens same (housing chamber)) USPAT: US-PGFUB 2003/08/07 USPAT: US-PGFUB 2003/08/07 USPAT: US-PGFUB 2003/08/07 USPAT: USPA	_	30	((denosition near chamber) and mlaten)		1
Section   Community   Commun	-	30			- · · · , · · · , - ·
September   Sept	_	5			
193			, , , , , , , , , , , , , , , , , , ,		1 '
193	-	892	cvd and (lens same (housing chamber))	USPAT;	2003/08/07
and (inert and nitrogen) 0 ((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and venturi 10 (cvd and (lens same (housing chamber))) and venturi 111 cvd and venturi 112 (cvd and venturi) and (venturi same vacuum) 113 (cvd and venturi) and (venturi same vacuum) ((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum 114 (cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum 115 (cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum) 116 ((cvd and venturi) and (venturi same vacuum)) and (inert and nitrogen)) and vacuum) 117 (((cvd and venturi)) and (venturi same vacuum)) and (inert and nitrogen)) and vacuum) 118 (((cvd and venturi)) and (venturi same vacuum)) and (inert and nitrogen)) and vacuum)) and (inert and nitrogen)) and (inert and nitrogen) 119 (((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and (inert and nitrogen)) and vacuum and (inert and nitrogen)) and (inert and nitrogen) and (inert					
0	-	193		1	1
and (inert and nitrogen)) and venturi  (ovd and (lens same (housing chamber))) and venturi  (cvd and venturi)  (cvd and venturi)  (cvd and venturi)  (cvd and venturi)  169 (cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum  (cvd and venturi) and (venturi same vacuum)) (((cvd and venturi) and (venturi same vacuum)) and (nozzle and valve)  - 48 (((cvd and venturi) and (venturi same vacuum)) and (nozzle and valve) - 17 ((((cvd and venturi) and (venturi same vacuum)) ((((cvd and (lens same (housing chamber)) and ((platen platform stage support) same (reference standard\$ datum))  - ((platen platform stage support) same (reference standard\$ datum)) - (((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)  - 3 (((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and venturi - 211 (((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and (platen platform stage support) same (reference standard\$ datum))  - 42 ((((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and (platen platform stage support) same (reference standard\$ datum)) and (vacuum and nozzle)  - 42 ((((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and (platen platform stage support) same (reference standard\$ datum)) and (vacuum and nozzle)  - 42 ((((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and (platen platform stage support) same (reference standard\$ datum)) and (vacuum and nozzle)  - 50 (336080.uRPN.  - 5003/08/07  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09  22:09					
0   (cvd and (lens same (housing chamber))   0   0   0   0   0   0   0   0   0	-	"		1	
and venturi   191   22:00   203/08/07   77   (cvd and venturi) and (venturi same vacuum)   169   (cvd and (lens same (housing chamber))   22:01   203/08/07   22:01   203/08/07   22:01   203/08/07   22:01   203/08/07   22:01   203/08/07   22:01   203/08/07   22:01   203/08/07   22:01   203/08/07   22:01   203/08/07   22:01   203/08/07   22:01   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:02   203/08/07   22:03   203/08/07   22:03   203/08/07   22:03   203/08/07   22:03   203/08/07   22:03   203/08/07   22:03   203/08/07   22:03   203/08/07   22:03   203/08/07   22:03   203/08/07   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03   22:03	_	٥ ا		,	1
169				1	
To   Cove and venturi) and (venturi same vacuum)   Cove and (lens same (housing chamber))   Cove and vacuum)   Cove and vacuum   Cove and	_	191	cvd and venturi	USPAT;	2003/08/07
Vacuum   ((cvd and (lens same (housing chamber))   and (inert and nitrogen)) and vacuum   ((cvd and venturi) and (venturi same vacuum)) (((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum   (((cvd and venturi) and (venturi same vacuum)) (((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum)   (((cvd and (lens same (housing chamber))) and ((nozzle and valve))   (((cvd and venturi) and (venturi same vacuum)) and (nozzle and valve)   (((cvd and (lens same (housing chamber))) and ((platen platform stage support) same (reference standard\$ datum))   (((semiconductor wafer) and (lens same (housing chamber))   (((semiconductor wafer)) and (inert and nitrogen)) and (vacuum)   (((semiconductor wafer)) and (inert and nitrogen)) and (vacuum)   (((semiconductor wafer))   ((semiconductor wafer))   (semiconductor wafer))   (semiconductor wafer))   (semiconductor wafer)   (semiconductor wafer))   (semiconducto					
169	-	77			
and (inert and nitrogen)) and vacuum (Covd and venturi) and (venturi same vacuum) (((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum) (((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum) (((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum) and (nozzle and valve) and ((cvd and venturi) and (venturi same vacuum)) (((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum)) and (nozzle and valve) and ((platen platform stage support) same (reference standards datum)) and ((platen platform stage support) same (housing chamber)) and (inert and nitrogen) and vacuum) and (inert and nitrogen)) and (inert and nitrogen) a		1.60			
246	-	169			
Vacuum  (((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and (vacuum)   (((cvd and venturi) and (venturi same vacuum)) (((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum) and (nozzle and valve) ((((cvd and venturi) and vacuum)) and (nozzle and valve) (vacuum)) and (nozzle and valve) (vacuum)) and (inert and nitrogen)) and (inert and nitrogen)) and (inert and nitrogen)) and (inert and nitrogen)) and (inert and nitrogen) and ((platen platform stage support) same (reference standard) adminitrogen)   ((semiconductor wafer) and (lens same (housing chamber)) and (inert and nitrogen))   ((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen))   (((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen))   and (inert and nitrogen)   and (inert and	_	246			
Chamber ) and (inert and nitrogen) and vacuum)   vacuum)   (((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum)) and (nozzle and valve)   ((((cwd and venturi) and (venturi same vacuum)) and (nozzle and valve)) and ((platen platform stage support) same (reference standard\$ datum))   ((semiconductor wafer) and (lens same (housing chamber)))   (((semiconductor wafer) and (lens same (housing chamber)))   ((((semiconductor wafer) and (lens same (housing chamber)))   ((((semiconductor wafer) and (lens same (housing chamber)))   (((((semiconductor wafer) and (lens same (housing cham	1	]		1	
48			chamber))) and (inert and nitrogen)) and		
Vacuum) (((cvd and (lens same (housing chamber))) and (inert and nitrogen)) and vacuum)) and (nozzle and valve) ((((cvd and venturi) and (venturi same vacuum)) and (inert and nitrogen)) and vacuum)) and (inert and nitrogen)) and (inert and nitrogen)) and ((platen platform stage support) same (reference standard\$ datum)) ((semiconductor wafer) and (lens same (housing chamber)) ((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and (inert and nitrogen)) and ((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and venturi (((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and (platen platform stage support) same (reference standard\$ datum)) and (vacuum and nozzle) ((((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and ((platen platform stage support) same (reference standard\$ datum)) and (vacuum and nozzle) (((((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and ((platen platform stage support) same (reference standard\$ datum)) and (vacuum and nozzle) (((((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and ((platen platform stage support) same (reference standard\$ datum)) and (vacuum and nozzle) (((((semiconductor wafer) and (lens same (housing chamber))) and (inert and nitrogen)) and ((platen platform stage support) same (reference standard\$ datum)) and (vacuum and nozzle) (uspat; uspat; us			l '		
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- 446 (356/36).CCLS. USPAT; 2003/08/08		140	(200/301,320/.00ш).	,	
	_	446	(356/36).CCLS.		

-	400	(156/345.12,345.13,345.15).CCLS.	USPAT;	2003/08/08
_	1196	((359/509).CCLS.) ((250/431,428).CCLS.)	US-PGPUB USPAT;	15:22   2003/08/10
	1130	((356/36).CCLS.)	US-PGPUB	20:38
		((156/345.12,345.13,345.15).CCLs.)		
-	8	(((359/509).CCLS.) ((250/431,428).CCLS.)	USPAT;	2003/08/08
		((356/36).CCLS.) ((156/345.12,345.13,345.15).CCLS.)) and	US-PGPUB	15:24
		((cvp cmp polish\$ etch\$) and (lens same		
		(housing chamber)))		
-	5807	((cvp cmp polish\$ etch\$) and (lens same	USPAT;	2003/08/10
		(housing chamber)))	US-PGPUB	20:50
-	92	(((cvp cmp polish\$ etch\$) and (lens same (housing chamber)))) and ((standard	USPAT; US-PGPUB	2003/08/08
		reference calibra\$) near (slice wafer	US-PGPUB	16:21
		substrate))		
-	8	((((cvp cmp polish\$ etch\$) and (lens same	USPAT;	2003/08/08
		(housing chamber)))) and ((standard	US-PGPUB	15:25
		reference calibra\$) near (slice wafer		
_	16	substrate))) and (nitrogen and inert)   (((cvp cmp polish\$ etch\$) and (lens same	USPAT;	2003/08/08
	10	(((cvp cmp polish; etch;) and (lens same (housing chamber)))) and venturi	US-PGPUB	16:22
-	92	(((cvp cmp polish\$ etch\$) and (lens same	USPAT;	2003/08/08
		(housing chamber)))) and ((standard	US-PGPUB	16:22
		reference calibra\$) near (slice wafer		
_	16	substrate))   (((cvp cmp polish\$ etch\$) and (lens same	USPAT;	2003/08/08
_	16	(((cvp cmp polish; etch;) and (lens same (housing chamber)))) and venturi	US-PGPUB	16:22
_	108	((((cvp cmp polish\$ etch\$) and (lens same	USPAT;	2003/08/08
		(housing chamber)))) and ((standard	US-PGPUB	16:23
		reference calibra\$) near (slice wafer		
		substrate)) ) ((((cvp cmp polish\$ etch\$)   and (lens same (housing chamber)))) and		
		venturi )		
-	92	(((((cvp cmp polish\$ etch\$) and (lens	USPAT;	2003/08/08
		same (housing chamber)))) and ((standard	US-PGPUB	16:27
		reference calibra\$) near (slice wafer		
		substrate)) ) ((((cvp cmp polish\$ etch\$)   and (lens same (housing chamber)))) and		
		venturi   ) and (inert nitrogen nozzle		
		valve vacuum)	:	
-	25	(((((cvp cmp polish\$ etch\$) and (lens	USPAT;	2003/08/08
		same (housing chamber)))) and ((standard	US-PGPUB	16:24
		reference calibra\$) near (slice wafer substrate)) ) ((((cvp cmp polish\$ etch\$)		
		and (lens same (housing chamber)))) and		
		venturi )) and ((inert nitrogen) and		
		(nozzle valve vacuum))		2002/02/22
_	67	<pre>((((((cvp cmp polish\$ etch\$) and (lens same (housing chamber)))) and ((standard</pre>	USPAT; US-PGPUB	2003/08/08
		reference calibra\$) near (slice wafer	03-FGF0B	10.27
}		substrate))) ((((cvp cmp polish\$ etch\$)		
		and (lens same (housing chamber)))) and		
		venturi )) and (inert nitrogen nozzle		
		<pre>valve vacuum)) not (((((cvp cmp polish\$ etch\$) and (lens same (housing</pre>		
		chamber)))) and ((standard reference		
		calibra\$) near (slice wafer substrate)) )		
		((((cvp cmp polish\$ etch\$) and (lens same		
		(housing chamber)))) and venturi )) and		
		((inert nitrogen) and (nozzle valve vacuum)))		
-	723	(cvp cmp polish\$3 etch\$3) and (dummy near	USPAT;	2003/08/10
		(holder stage platform platen wafer))	US-PGPUB	20:41
-	1196	((359/509).CCLS.) ((250/431,428).CCLS.)	USPAT;	2003/08/10
		((356/36).CCLS.) ((156/345.12,345.13,345.15).CCLS.)	US-PGPUB	20:38
	<u> </u>	1 (1200, 010.12, 010.10, 010.10,	.1	

		177	Transm.	10003/00/10
-	6	((cvp cmp polish\$3 etch\$3) and (dummy	USPAT;	2003/08/10
		near (holder stage platform platen	US-PGPUB	20:38
		wafer))) and (((359/509).CCLS.)		
		((250/431,428).CCLS.) ((356/36).CCLS.)		
		((156/345.12,345.13,345.15).CCLS.))	ucpam.	2002/09/10
-	23	((cvp cmp polish\$3 etch\$3) and (dummy	USPAT;	2003/08/10
		near (holder stage platform platen	US-PGPUB	20:42
		wafer))) and (lens same (housing		
		chamber))	IIGDAM -	2003/08/10
_	23		USPAT;	
		near (holder stage platform platen	US-PGPUB	20:42
		wafer))) and (lens same (housing		
		chamber))) not (((cvp cmp polish\$3		
		etch\$3) and (dummy near (holder stage		
		platform platen wafer))) and		
		(((359/509).CCLS.) ((250/431,428).CCLS.)		
		((356/36).CCLS.)		
	F007	((156/345.12,345.13,345.15).CCLS.)))	HCDATT.	2003/08/10
-	5807		USPAT;	1
	(70	(housing chamber)))	US-PGPUB	20:51 2003/08/10
-	672	(((cvp cmp polish\$ etch\$) and (lens same	USPAT;	2003/00/10
		(housing chamber))) ) and ((first second\$3 primary another other two) near	US-PGPUB	20:52
	1	(platen platform stage support chuck))	IICDAM.	2003/08/10
_	1	1 , , , , , , , , , , , , , , , , , , ,	USPAT; US-PGPUB	20:53
		((356/36).CCLS.)	US-PGPUB	20:53
		((156/345.12,345.13,345.15).CCLS.)) and (((cvp cmp polish\$ etch\$) and (lens same		
	l	((((CVP cmp polish; etch;) and (lens same (housing chamber))) ) and ((first	İ	
		second\$3 primary another other two) near		
		(platen platform stage support chuck)))		
_	242		USPAT;	2003/08/10
-	242	(housing chamber)))) and ((first	US-PGPUB	20:53
		second\$3 primary another other two) near	05-FGF0B	20.33
		(platen platform stage support chuck)))		
	ļ	and (nitrogen inert)	1	
<u>_</u>	160		USPAT;	2003/08/10
	100	same (housing chamber))) ) and ((first	US-PGPUB	20:53
		second\$3 primary another other two) near	55 15155	20.00
		(platen platform stage support chuck)))		
1		and (nitrogen inert)) and (extract\$		
		exhaust)	1	
l _	56		USPAT;	2003/08/10
		same (housing chamber))) ) and ((first	US-PGPUB	20:55
		second\$3 primary another other two) near	35 13102	-3.00
	i	(platen platform stage support chuck)))	1	
		and (nitrogen inert)) and (extract\$		
[		exhaust)) and nozzle		
_	51		USPAT;	2003/08/10
		same (housing chamber))) ) and ((first	US-PGPUB	20:55
]		second\$3 primary another other two) near	35 13132	-3.00
		(platen platform stage support chuck)))		
		and (nitrogen inert)) and (extract\$		
		exhaust)) and nozzle) and valve		1
t	<u> </u>	Citianoli and modulo, and valve	1	<u> </u>